

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

AKIRA GODA, ET AL.

: GROUP ART UNIT: 2822

SERIAL NO: 09/556,777

RCE FILED: HEREWITH

: EXAMINER: SOWARD, I.

FOR: NONVOLATILE SEMICONDUCTOR

MEMORY DEVICE AND METHOD

FOR MANUFACTURING THE SAME

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

In response to the Office Action dated July 3, 2002, please amend the above-identified application as follows:

IN THE CLAIMS

Please amend Claims 1, 20, and 22 as shown in clean form below.¹

1. (Twice Amended) A nonvolatile semiconductor memory device comprising:

a semiconductor substrate;

an element isolation region formed in the semiconductor substrate, the element isolation region isolating a plurality of element regions in the semiconductor substrate;

a first transistor formed in a peripheral circuit portion of the semiconductor substrate, the first transistor including source and drain diffusion layers formed in one of the plurality of element regions and a gate electrode having a first gate length;

¹A marked-up copy of the amended portion of the claims is attached hereto.

shorter gate length